

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re the Application of: **Miwa KOZAWA et al.**

Art Unit: **1795**

Application Number: **10/720,097**

Examiner: **Daborah Chacko Davis**

Filed: **November 25, 2003**

Confirmation Number: **4454**

For: **PROCESS FOR FORMING RESIST PATTERN, SEMICONDUCTOR DEVICE  
AND FABRICATION THEREOF**

Attorney Docket Number: **032132**

Customer Number: **38834**

**AMENDMENT UNDER 37 C.F.R. §1.114**

**Mail Stop: RCE**

October 9, 2009

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

In response to the Office Action dated June 11, 2009, this submission being filed concurrently with a Request for Continued Examination under 37 C.F.R. §1.114 and the response date of which having been extended by one month to October 11, 2009, Applicants amend the claims as follows and submit the following remarks.

Amendments to the Claims begin on page 2 of this paper.

Remarks/Arguments begin on page 9 of this paper.